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APPENDIX

Apendix - A

DATA FROM SCANNING ELECTRON MICROSCOPE

The film thickness of deposited film at different conditions

(1) The effect of %photoinitiator

% Photoinitiator (w/v)	Thickness (μm)			Average (μm)
0.5	4.88	4.94	4.88	4.90
1.0	6.53	6.69	6.53	6.6
1.5	22.3	22.4	22.1	22.3
2.0	88.4	89.0	88.4	88.6
2.5	101.0	100.0	99.0	100.0

(2) The effect of deposition time

Deposition time (hrs)	Thickness (μm)			Average (μm)
2	85.6	84.4	84.4	84.8
4	94.5	96.9	94.4	95.3
6	121.0	121.0	121.0	121.0
8	157.0	158.0	159.0	158.0
10	158.0	160.0	164.0	160.7

(3) The effect of irradiation time

Irradiation time (hrs)	**Thickness (μm)**			**Average (μm)**
2	63.8	62.0	62.8	62.9
4	98.0	96.8	96.8	97.2
6	86.2	85.6	84.4	85.4
8	48.2	49.0	48.2	48.5
10	5.84	5.84	5.66	5.8

(4) The effect of substrate temperature

Substrate temp (K)	**Thickness (μm)**			**Average (μm)**
263	149.0	147.0	149.0	148.3
273	120.0	122.0	118.0	120.0
278	112.0	100.0	109.0	107.0
283	29.4	25.4	25.4	26.7
298	0	0	0	0

(5) The effect of N_2 flow rate

N_2 flow rate (ml/min)	**Thickness (μm)**			**Average (μm)**
20	14.3	13.1	13.1	14.3
40	27.6	27.6	26.8	27.3
70	68.0	66.6	67.2	67.3
90	93.7	96.9	94.4	95.0
110	102	99.0	99.0	100.0

Appendix - B

DATA FROM GEL PERMEATION CHROMATOGRAPHY

The molecular weight of deposited film at different conditions

(1) The effect of % photoinitiator

%Photoinitiator (w/v)	Molecular weight
0.5	213839
1.0	261583
1.5	287165
2.0	330043
2.5	371346

(2) The effect of deposition time

Deposition time (hrs)	Molecular weight
2	149756
4	209467
6	272148
8	343090
10	447330

(3) The effect of substrate temperature

Substrate temperature (K)	**Molecular weight**
263	295828
273	197837
278	184805
283	116202
298	0

(4) The effect of N_2 flow rate

N_2 flow rate (ml/min)	**Molecular weight**
22	41634
40	109303
70	130709
90	209467
110	392219

Apendix - C

THE ESTIMATION OF FILM THICKNESS BY SCANNING ELECTRON MICROSCOPE

The film thickness can be measured from the rough estimation by SEM

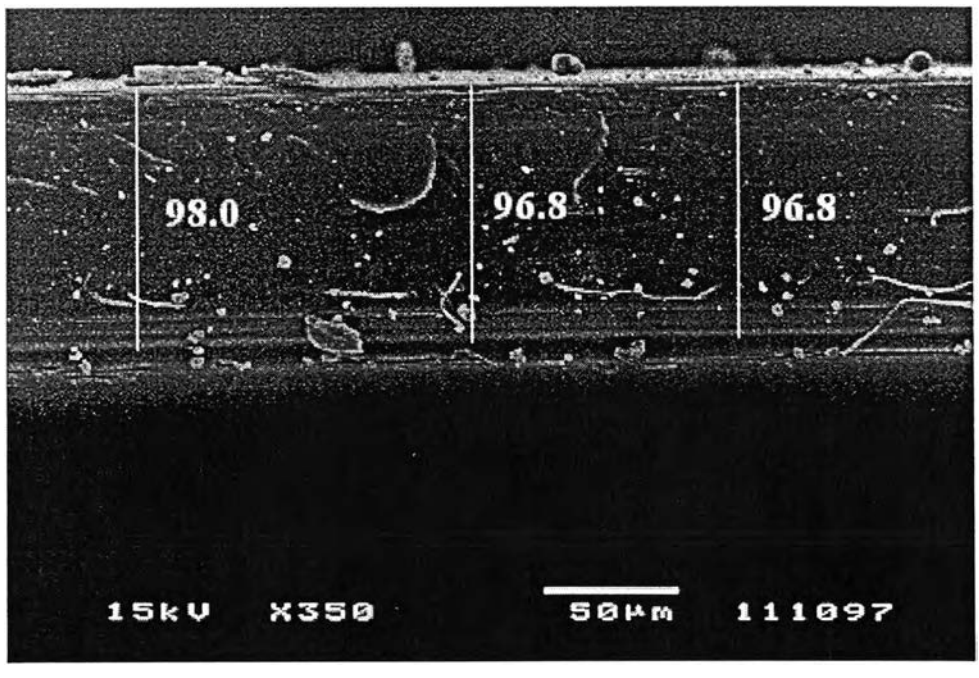

Figure C.1 Estimation of film thickness by SEM

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